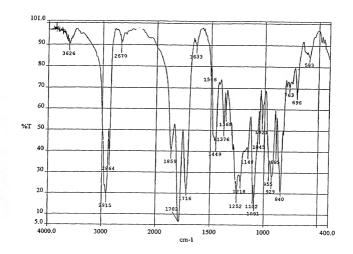
Inventor Name: Taeko IDEGAWA et al.
Title of Inventor: NOVEL COPOLYMER, PHOTORESIST COMPOSITION,
AND PROCESS FOR FORMING RESIST PATTERN WITH HIGH ASPECT RATIO
PRING DEM: 120 11, 12001
SMZZMČS REF. No.: Q65210

SMZM&S Ref. No.: Q65210 SMZM&S Tel. No.: (202) 293-7060 Sheet 1 of 2

## FIG. I



## 042815-2.PK

042815-2.SP 3601 4000.0 400.0 6.3 100.0 4.0 %T 8 3.0

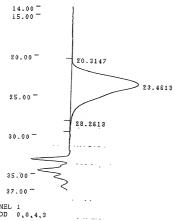
REF 4000 97.0 2000 88.8 600

36269 90.1 2915.5 19.9 2864.1 37.9 2670.0 91.1 1859.1 40.8 1782.3 6.3 1716.3 21.7 1633.7 88.8 1506.0 77.5 1449.8 42.9 1376.8 52.2 1360.3 57.1 1252.0 19.5 1218.2 25.2 1148.3 38.4 1102.8 18.0 1091.1 18.3 1045.0 48.6 1021.6 52.9 955.2 30.1 929.9 27.9 885.8 39.9 840.0 20.6 763.8 70.4 696.1 66.9 583.4 84.7

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## FIG. 2



METHOD	0,0,4,3	
CALIBRAT	TION OFF	

NO. NAME  1 2 3 TOTAL	RET TIME 20.3147 23.4613 28.2613	AREA 96.1 2280773.8 7062.7	М	ID# I 1 I 2 I 3	CONC 96.1277 2280773.7500 7082.6392	
IUTAL		2287932.8			2287932 5770	100 0000

## CALIBRATION DATA

3 ORDER REGRESSION

LOG M = a\*T^3+b\*T^2+c\*T^1+d a = -6.509859E-004 -...

b = · 5.063016E-002

d = -1.552977E+000 d = 2.123975E+001

"PEAK TOP RT = 23.5750 : M = MN = 11243 . MW = 18729

MW/MN = 1.6658 MZ = 27080 MZ/MN = 2.4082